

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8925	430/311-313,394.ccls.	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 09:53
L2	451	1 and (interlac\$3 or intertwi \$3 or double expos\$3)	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 09:56
L3	4800	1 and @ad<="20010510"	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:01
L4	162	2 and 3	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:01
L5	284	1 and 3 and (second or another or additional or extra or overlap\$4 or separate or different) (expos \$3) same (photoresist or resist) not 4	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:04
L6	61	1 and 3 and (develop\$4) same (photoresist or resist) same etch\$3 same (semiconductor or wafer) and (dynamic random access memory or DRAM) not 4 not 5	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:05
L7	59	1 and 3 and (round\$3 near corner or line near3 shorten \$3) not 4 not 5 not 6	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:06
L8	32	1 and 3 and (optical proximity near2 (correct\$3 or effect) or OPC) not 4 not 5 not 6 not 7	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:07
L9	1767	430/22.ccls. not 1	US- PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:08

L10	111	(1 or 9) and 3 and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((double or two or second or overlap\$4 or stitch\$3 or overlay\$3 or over) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:10
L11	418	(1 or 9) and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:13
L12	34	(Hwang-Jiunn-Ren or Chen-Anseime or Huang-I-Hsiung). in. and (United Microelectronics).as. not 4 not 5 not 6 not 7 not 8 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:20
L13	48	((Hwang-Jiunn-Ren or Chen-Anseime or Huang-I-Hsiung). in. or (United Microelectronics).as.) and (photoresist or resist) same (((double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 expos\$3) and develop\$4) not 4 not 5 not 6 not 7 not 8 not 10 not 11 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:21
L14	12	(1 or 9) and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((multipl\$3 or plural\$3) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/10/09 10:23

L15	2	(((interlac\$3 or intertwin\$3 or double or second or another or additional or extra or overlap\$4 or separate or different) (expos\$3) and (photoresist or resist) or ("same" or single or singular or first or one) near2 (photoresist or resist) and (double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 (expos\$3))) and develop\$4 and etch\$3 and (semiconductor or wafer) and (dynamic random access memory or DRAM) and (round\$3 near corner or line near3 shorten\$3 or (optical proximity near2 (correct\$3 or effect) or OPC))).clm.	US-PGPUB; USPAT	ADJ	ON	2008/10/09 11:21
L16	7	((((interlac\$3 or intertwin\$3 or double or second or another or additional or extra or overlap\$4 or separate or different) (expos\$3) and (photoresist or resist) or ("same" or single or singular or first or one) near2 (photoresist or resist) and (double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 (expos\$3))) and develop\$4 and etch\$3 and (semiconductor or wafer) and (dynamic random access memory or DRAM))).clm. not 15	US-PGPUB; USPAT	ADJ	ON	2008/10/09 11:23

10/9/08 11:26:09 AM

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